Special Issue

Advanced Photodetectors: Materials, Design and Applications

Message from the Guest Editors

We invite researchers in the field of photodetectors to submit their innovative work for consideration in our upcoming Special Issue "Advanced Photodetectors: Materials, Design, and Applications". This Special Issue aims to provide a platform for showcasing cutting-edge advancements in photodetector technology. We encourage submissions related to:

- Materials: Explore novel materials that are revolutionizing photodetection, from traditional semiconductors to emerging nanomaterials and organic compounds.
- Design: Present your research on innovative photodetector designs, including plasmonic structures, quantum dot-based architectures, and beyond.
- Applications: Demonstrate the practical relevance of advanced photodetectors in various domains, such as optical communications, imaging, remote sensing, and biomedical applications.

By submitting your contributions to this Special Issue, you will join a dynamic community of experts pushing the boundaries of photodetector technology. Your research will help bridge the gap between materials science, design innovation, and practical applications.

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Deadline for manuscript submissions

15 June 2025

Micromachines

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About the Journal

Message from the Editor-in-Chief

You are invited to contribute research articles or comprehensive reviews for consideration and publication in *Micromachines* (ISSN 2072-666X). *Micromachines* is published in the open access format. Research articles, reviews and other contents are released on the internet immediately after acceptance. The scientific community and the general public have unlimited free access to the content as soon as it is published. As an open access journal, *Micromachines* is supported by the authors or their institutes by payment of article processing charges (APC) for accepted papers. We are pleased to welcome you as our authors.

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